

Inventor: Leonard Forbes  
Title: Electronic Apparatus, Silicon-On-Insulator Integrated Circuits, and Fabrication Methods  
Assignee: Micron Technology, Inc.  
Docket No. MI22-2272

### INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

#### REMARKS

The citations listed, copies attached except for U. S. Patents, may be material to the examination of the subject application and are therefore submitted in compliance with the duty of disclosure defined in 37 CFR §1.56. The Examiner is requested to make these citations of official record in this application. No admission is made regarding

The materials cited are presented to assist in and expedite examination of this application. The present invention is considered to be patentable over the cited materials. Expeditious examination and allowance of this application as a patent are therefore urged in order that the public may benefit from the disclosure and commercialization of the invention.

Respectfully submitted,

Dated: 24 Sep 2003

Attorney: 

James E. Lake  
Reg. No.: 44,854

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2272	SERIAL NO. Filed Herewith
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Leonard Forbes	
				FILING DATE Filed Herewith	GROUP Unknown

  

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	4,241,359	12/23/1980	Izumi et al			
	AB	5,441,591	08/15/1995	Forbes			
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	AG						
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FOREIGN PATENT DOCUMENTS							
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						Yes	No
	AM						
	AN						
	AO						
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	10/443,335		Forbes			05/21/2003	
	AB							
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	AA	S.S.K. Iyer et al., "Separation by Plasma Implantation of Oxygen (SPIMOX) operational phase space," IEEE trans. On Plasma Science, Vol. 25, No.5, pp. 1128-135, 1997			
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	AF	"Materials Selector", Reinhold Publishing Co., Penton/IPC. <a href="http://www.handyharmancanada.com/TheBrazingBook/comparis.htm">http://www.handyharmancanada.com/TheBrazingBook/comparis.htm</a>			
	AG	Company page <a href="http://www.hithermaln.com/datasheets/index.cfm?page=values">http://www.hithermaln.com/datasheets/index.cfm?page=values</a>			
	AH	R. People et al, "Calculation of Critical Layer Thickness Versus Lattice Mismatch for Ge <sub>2</sub> Si <sub>1-x</sub> /Si Strained Layer Heterostructures, "Appl. Phys. Letters, Vol. 47, P. 322-324, August 1985.			
	AI	R. People et al, "Erratum: Calculation of Critical Layer Thickness Versus Lattice Mismatch for Ge <sub>2</sub> Si <sub>1-x</sub> /Si Strained Layer Heterostructures, "Appl. Phys. Letters, Vol. 49, P. 229, July 1986.			
	AJ	G. Grenet et al., "Testing the Feasibility of Strain Relaxed Compliant Substrates," Abstract of Electronic Materials Conference, Santa Barbara, June 2002, P.8.			
	AK	K.D. Hobart et al, "High Ge-Content Relaxed Si <sub>1-x</sub> Ge <sub>x</sub> Layers by Relaxation on Compliant Substrate with Controlled Oxidation," Abstract of Electronic Materials Conferences, Santa Barbara, June 2002, pp. 8.			
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	AM	A.J. Auberton-Herve, "SOI: Materials to Systems," Digest of the International Electron Device Meeting, San Francisco, December 1996, pp. 5-10			
	AN	T. Tsuchida et al., "Self-combustion Reaction Induced by Mechanical Activation of Al-si-c Powder Mixtures," European Journal of Solid State and Inorganic Chemistry (France), Vol. 32, No. 7-8, pp. 629-38, 1995.			
	AO	H.C. Yi, et al, "Combustion Synthesis of Aluminoborate Glass Matrices," J. Mater. Synth. Process. (USA), Vol. 8, No. 1, pp. 15-20, Jan. 2000.			
	AP	Dip. -Ing. M. Wild, Dr. -Ing. A. Gillner, "Laser Assisted Bonding of Silicon and Glass in Micro-System Technology," <a href="http://www.ilt.fhg.de/eng/jb00-s42.html">http://www.ilt.fhg.de/eng/jb00-s42.html</a>			
	AQ	Saman Dharmatilleke et al, "Anodic Bonding of Glass to Glass and Silicon to Glass or Silicon to Silicon Through a Very Thick Thermally Grown SiO <sub>2</sub> Layer," <i>Proceedings of IS 3M International Symposium on Smart Structures &amp; Microsystems</i> , Hong Kong, October 19-21, 2000, p. 32. <a href="http://dolphin.eng.us.edu/projects/bonding/paper.pdf">http://dolphin.eng.us.edu/projects/bonding/paper.pdf</a>			
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